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AMENDMENTS TO THE CLAIMS

Listing of the Claims:

1. (Currently amended) A system for controlling a thin film deposition process, comprising:
 - one or more thin film deposition components that deposit a thin film on one or more portions of a wafer;
 - a thin film deposition component driving system for driving the one or more deposition components;
 - a system for directing light on to the deposited thin film and collecting light reflected from the deposited thin film;
 - a scatterometry system that detects structural irregularities associated with the deposited thin film by comparing reflected light data associated with the deposited thin film with a database comprising known thin film reflected light signatures; and
 - a processor that communicates with the scatterometry system and the thin film deposition component driving system, wherein the processor partitions a mask into a plurality of grid blocks mapped to portions of on the wafer and determines deposition parameter adjustments at the one or more grid blocks for the one or more deposition components, the deposition parameter adjustments based at least in part upon data received from the scatterometry system.
2. (Previously presented) The system of claim 1, the scatterometry system captures the light reflected from the thin film.
3. (Previously presented) The system of claim 1, the structural irregularities associated with the thin film include at least one of pinholes, depressions, air bubbles, bumps, voids, agglomerates, large grains, second phase compositional variations and impurities, or a combination thereof.

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4. (Previously presented) The system of claim 1, the processor further determines the deposition parameter adjustments based in part on a presence of an unacceptable thin film deposition condition at the one or more grid blocks according to the data received from the scatterometry system.

5. (Previously presented) The system of claim 1, the deposition parameter adjustments comprise at least one of thickness, uniformity, rate of deposition, pressure, flow rates of reacting species, flow rate of carrier gas and temperature or a combination thereof.

6-27. (Canceled)

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28. (Currently amended) A method for monitoring and controlling the deposition of a thin film, comprising:

depositing ~~[[a]]~~ thin film at a plurality of portions of a mask associated with a wafer;

using a processor to partition the thin film into one or more grid blocks;

directing a light onto the one or more grid blocks of the thin film;

collecting a light reflected from the one or more grid blocks of the thin film;

employing scatterometry means to analyze the reflected light from the one or more grid blocks of the thin film to determine one or more properties of the one or more grid blocks of the thin film;

monitoring structural irregularities associated with the deposited one or more grid blocks of the thin film by comparing reflected light data associated with the deposited one or more grid blocks of the thin film with a database comprising known thin film reflected light signatures;

controlling a deposition component to deposit thin film at the one or more portions of on the wafer by utilizing a non-linear training system which facilitates determining deposition parameter adjustments according to the properties of the thin film; and

using ~~[[a]]~~ the processor to map the plurality of portions; to determine deposition conditions at the one or more ~~portions;~~ grid blocks and to control the at least one deposition component based at least in part on data received from the scatterometry means.

29. (Previously presented) The method of claim 28, the properties include at least one of thickness, uniformity, presence of defects, and presence of impurities or a combination thereof.

30-34. (Canceled)

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35. (Currently amended) A method for regulating a process for depositing a thin film, comprising:

using one or more deposition components to deposit a thin film;

using a processor to partition the thin film into one or more grid blocks;

determining the characteristics of the deposited thin film at the one or more grid blocks by utilizing reflected light to generate a signature and comparing the signature to known thin film reflected light signatures; and

using ~~[[a]]~~ the processor to map the one or more grid blocks of a mask of the thin film and to coordinate control of the one or more deposition components to deposit subsequent thin film ~~at the one or more grid blocks~~ film, the coordination based at least in part on the characteristics of the deposited thin film data gathered from comparing the reflected light from the one or more grid blocks to known thin film light signatures.

36. (Currently amended) A system for regulating a process for depositing a thin film, comprising:

means for using one or more deposition components to deposit a thin film;

means for determining the acceptability of the thin film deposition at one or more grid blocks by utilizing reflected light and comparing to known thin film reflected light signatures; and

means for using a processor to map the thin film into one or more grid blocks of a mask of the thin film and blocks, to coordinate control of the one or more deposition components to deposit the thin film ~~at the one or more grid blocks~~ film, and to determine the acceptability of the thin film deposition by comparing the known thin film signatures to reflected light.

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37. (Currently Amended) A system that controls the deposition of a thin film on a wafer, comprising:
- at least one deposition component employed to deposit a thin film at one or more ~~grid blocks~~ portions of a mask ~~mapped to portions of the wafer~~;
 - a coherent light source directed onto one or more grid blocks of the thin film;
 - a receiving component that collects light reflected from the one or more grid blocks of thin film;
 - a scatterometry system that analyzes the reflected light to determine one or more properties of the thin film at the one or more grid blocks; and
 - a processor that partitions the mask into the one or more grid blocks and controls the at least one deposition component based at least in part on data received from the scatterometry system.